

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit: To Be Assigned  
Examiner: To Be Assigned

In Re PATENT APPLICATION OF:

Applicants : Toyokazu Sakata

Serial No. : To Be Assigned

Filed : November 26, 2003

For : ETCHING METHOD AND  
SEMICONDUCTOR DEVICE  
FABRICATING METHOD

Attorney Ref. : TAI 145

**INFORMATION  
DISCLOSURE  
STATEMENT**

November 26, 2003

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

This is an information disclosure statement submitted in compliance with the timing requirements of 37 C.F.R. §1.97(b)(1).


Attached are copies of two Japanese patent publications and two English -language publications. Any relevance of the Japanese patents can be gleaned from the attached English-language Abstracts. The one of the Japanese publications and both English-language publications are listed on the attached Form PTO-1449 and discussed on pages 2 and 3 of the application. Also listed on the form PTO-1449 for consideration is one U.S. Patent. As the present application was filed after June 30, 2003, a copy of the U.S. Patent is not submitted with the Information Disclosure Statement, pursuant to the Notice of U.S. Patent & Trademark Office posted on the USPTO website on July 11, 2003.

Since this Information Disclosure Statement is being filed with the application, no certification or fee is required, and the requirements of 37 C.F.R. §§1.97 and 1.98 are deemed to be fully met as to the documents submitted. Consideration of the submitted and listed documents is respectfully requested.

Respectfully submitted,

November 26, 2003  
Date

SMR:tl

  
Steven M. Rabin (Reg. No. 29,102)  
RABIN & BERDO, P.C.  
CUSTOMER NO. 23995  
(202) 371-8976  
(202) 408-0924 fax

FEE ENCLOSED: \$  
Please charge any further  
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No. 18-0002

<b>FORM PTO-1449</b>  <b>INFORMATION DISCLOSURE STATEMENT</b>				Atty Docket		Application No.	
				<b>TAI 145</b>		<b>To Be Assigned</b>	
				Applicant			
				<b>Toyokazu Sakata</b>			
Filing Date				Group Unit			
<b>November 26, 2003</b>				<b>To Be Assigned</b>			
<b>U.S. PATENT DOCUMENTS</b>							
Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date
	AA	6,355,572	03/12/02	Ikegami			
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
<b>FOREIGN PATENT DOCUMENTS</b>							
		Document Number	Date	Country	Class	Sub-Class	Translation
	AK	7-94483	04/07/95	Japan			Abstract
	AL	2001-77086	03/23/01	Japan			Abstract
	AM						
	AN						
<b>OTHER (Including Author, Title, Date, Pertinent Pages, etc.)</b>							
	AO	<b>"Dry Etching of Organic Low Dielectric Constant Film without Etch Stop Layer"</b> <b>M.Mizumura et al. JJAP, Vol. 41, pp. 425-427</b>					
	AP	<b>"Highly Selective Etching of Organic SOG to SiN for Cu Damascene Interconnects Using New Gas Chemistry of C<sub>4</sub>F<sub>8</sub>/N<sub>2</sub>/Ar"</b> S. Uno et al. Proc. Of Dry Process Symp., pp. 215-220(1999)					
	AQ						
Examiner					Date Considered		
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.							